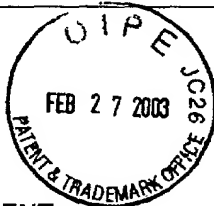


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**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

Applicant: Mandeep SINGH
Appln. No.: 09/605,657
Filing Date: June 28, 2000
Examiner: NGUYEN Group Art Unit: 2851

Date: February 27, 2003

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Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
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	JR					
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	LR					

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					Enclosed	No	Enclose	No
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HN	NR WO 98/28665	07/1998	PCT	LOOPSTRA et al.				
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HN	VR	Hudek et al., "E-beam and RIE examination of chemically amplified positive-tone resist CAMP6," <i>Microelectronic Engineering</i> 26:167-179 (1995), XP004000099			
HN	WR	Skulina et al., "Molybdenum/beryllium multilayer mirrors for normal incidence in the extreme ultraviolet," <i>Applied Optics</i> 34(19):3727-3730 (1995), XP000537295			
HN	XR	Mirkarimi et al., "Advances in the reduction and compensation of film stress in high-reflectance multilayer coatings for extreme ultraviolet lithography," <i>Proceedings of the SPIE</i> 3331:133-148 (1998), XP00900531			
	YR				
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Examiner H. Nguyen Date Considered: 3/8/03

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.